

Development of pixel sensors with $25 \times 500 \mu\text{m}^2$ pitch for the ATLAS HL-LHC upgrade

Presenter: Helen Hayward

Secondary Authors:

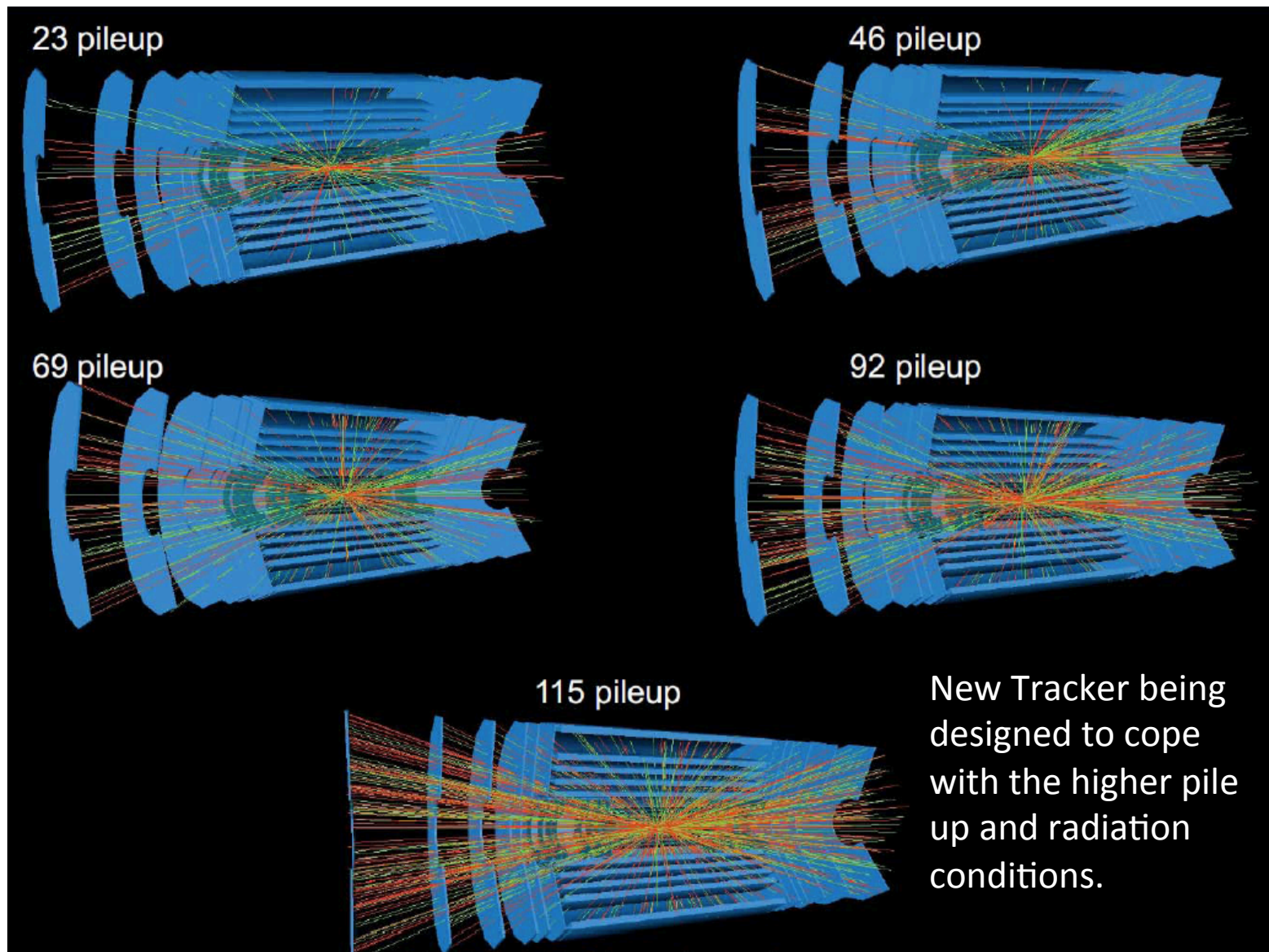
Dean Forshaw

Sergey Burdin, Gianluigi Casse

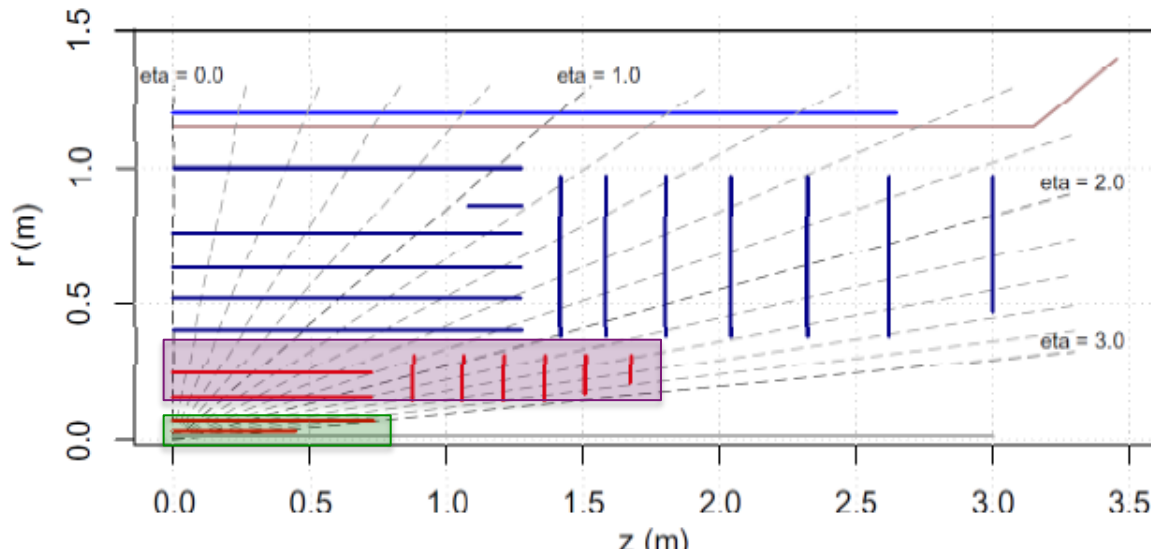


9th International "Hiroshima" Symposium on the Development and Application of Semiconductor Tracking Detectors, Hiroshima, Japan

- **Motivation:**
 - Upgrade of ATLAS tracker detector for the HL-LHC
- **Devices**
 - CERN Pixel V – alternative geometries
- **Performance**
 - Sensor performance
- **Conclusion**



ATLAS Itk – LOI design



- 4 pixel barrel layers
 - Radius from 39 mm to 250 mm
 - Z: ± 449 mm to ± 694 mm (outer 2 layers)
- 6 Pixel disks
 - $R_{\text{inner}} = 150$ mm
 - $R_{\text{outer}} = 315$ mm
 - Z: 820 mm to 1890 mm

2 outer Barrel layers / Disks

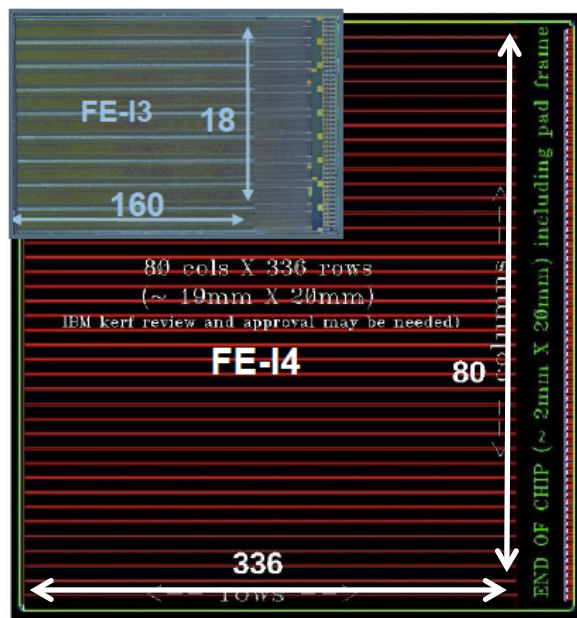
- Sensor
planar n-in-p
150 μm
- Pixel size **50 μm x 250 μm**
- ROIC thickness 150 μm
- ToT = 4 bits
- 2x2 (Quad) and 2x3 (Hex) chip modules
- Data rates of 640 Mbit/s per module

2 Inner Barrel layers

- Sensors
All sensor materials possible
150 μm silicon or thinner
- Pixel size **25 μm x 150 μm**
- ROIC thickness 150 μm
- ToT = 0-8 bits
- 2x1 and 2x2 chip modules
- 2x2 sensor = 33.9 mm x 40.6 mm
- Data rate as high as 2 Gbit/s per module

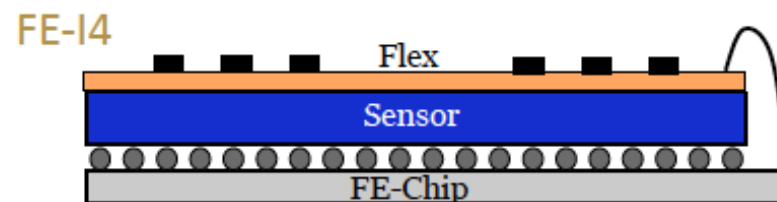
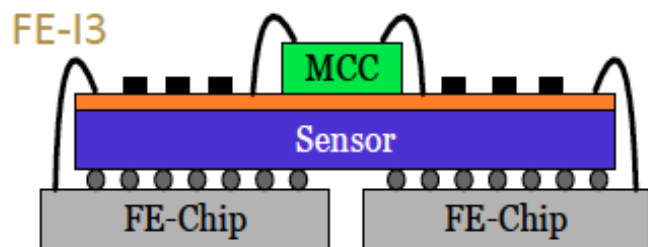
Goal

- The goal is to obtain the optimal pitch and thickness of pixel modules for different locations for the ITK.
- How do the pixels performance depend on the angle, irradiation and particle type ?
- The first step is to study the basic quantities for 0° and non-radiated sensors.
- Once we demonstrate we have the tools in place, we can proceed with high eta and radiated modules.
 - For different pitch and thickness sensors



FEI4 vs FEI3 specs

	FEI4	FEI3
Year	2011	2003
Technology	130nm	250nm
Chip Size	20x19mm ²	7.6x10.8mm ²
Active Area	89%	74%
Array	80x336 = 26,880	18x160 = 2,880
Pixel Size	50x250μm ²	50x400μm ²
N Transistors	87M	3.5M
Data Rate	320 Mb/s	40Mb/s
Wafer Yield	60%	80%



In production at Micron:

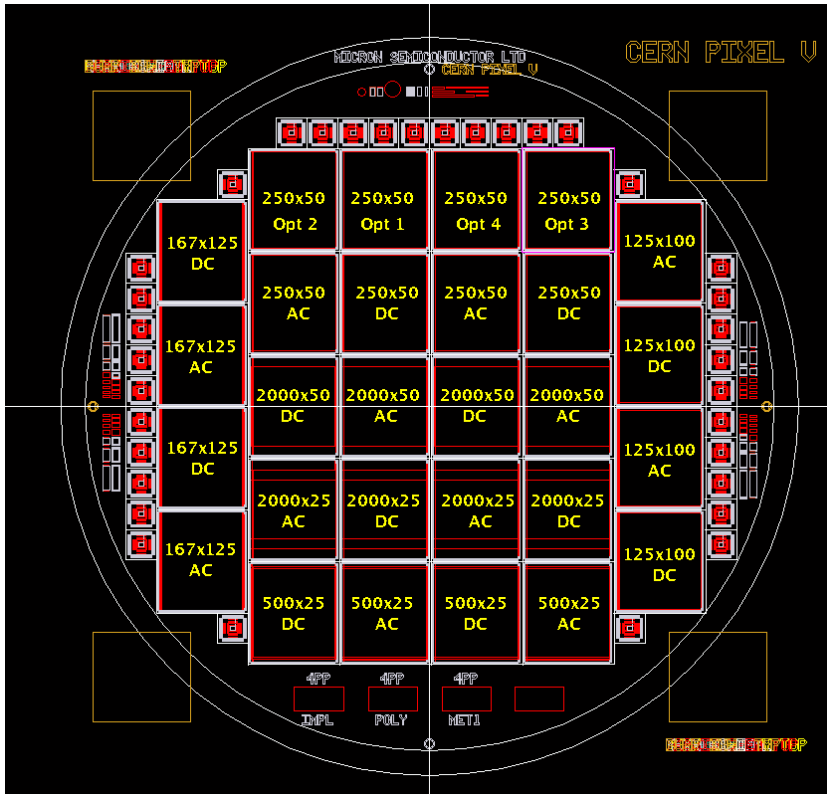
Segmentation:

- 125x100 μm (square)
- 167x125 μm (square)
- 250x50 μm (Standard)
- 500x25 μm (elongated)
- 2000x25 μm (strixel)
- 2000x50 μm (strixel)

Features both AC and DC power, polysilicon/
PTB

Production will be on 300, 200, 150, 100 μm

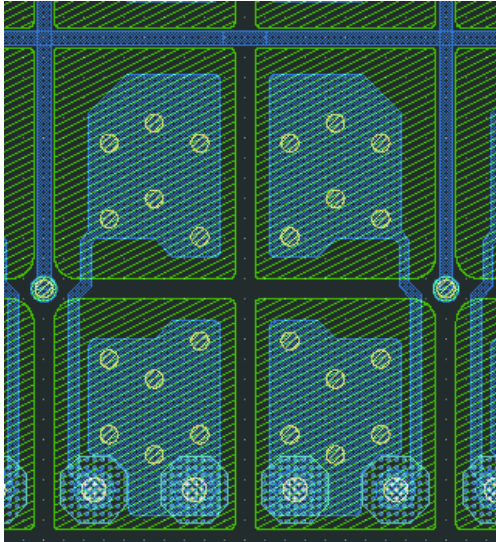
DC only wafers already produced and made
into working modules.



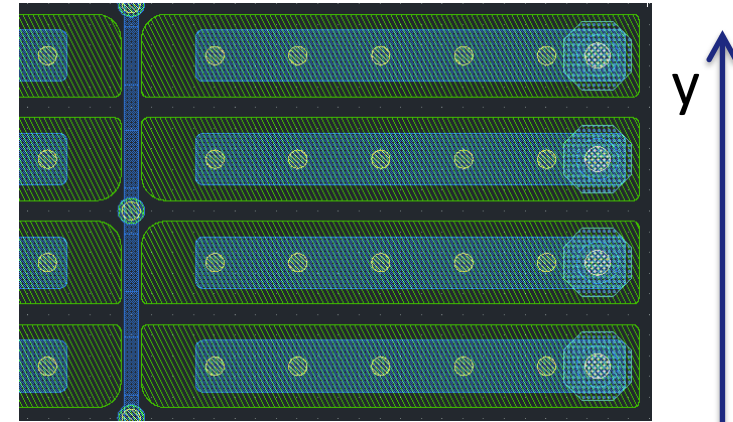
Fully finished AC/DC wafers across 4,10 and 13k Ω resistivity wafers expected mid to end of September, assembly production in weeks following

CERN PIXEL V – alternative geometries

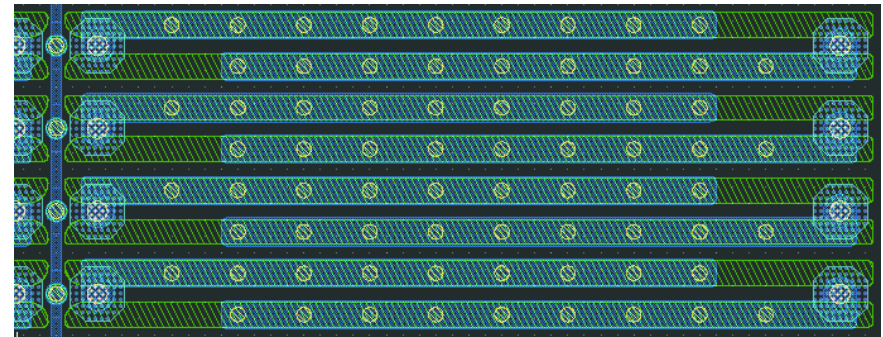
125x100 (square)



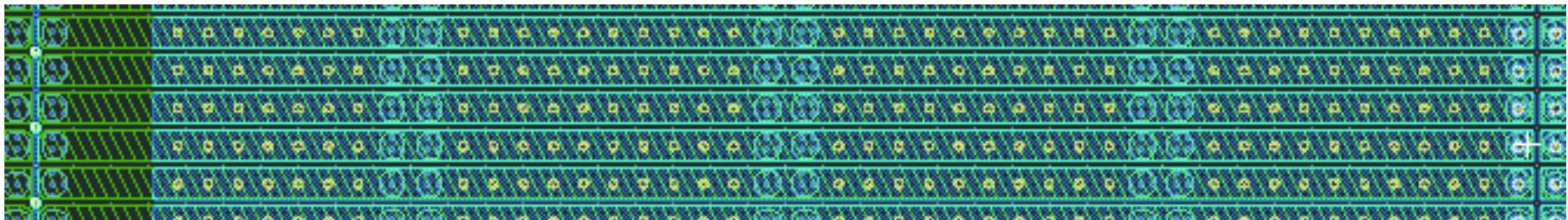
250x50
(VTT5)



500x25
(VTT10)

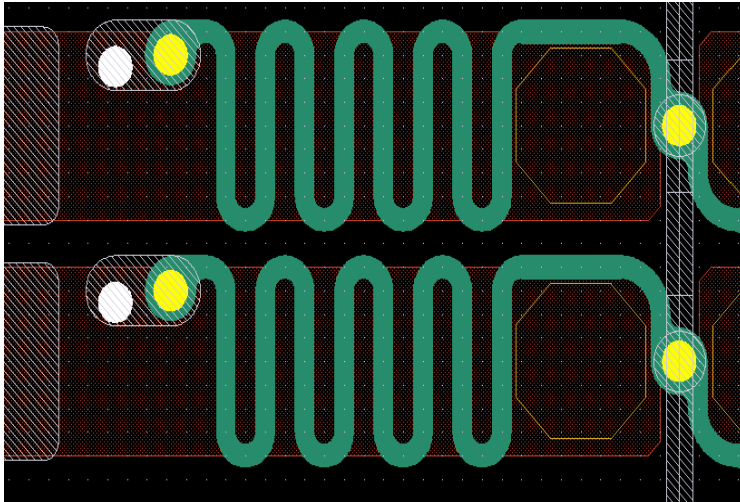


2000x50 (strixel)



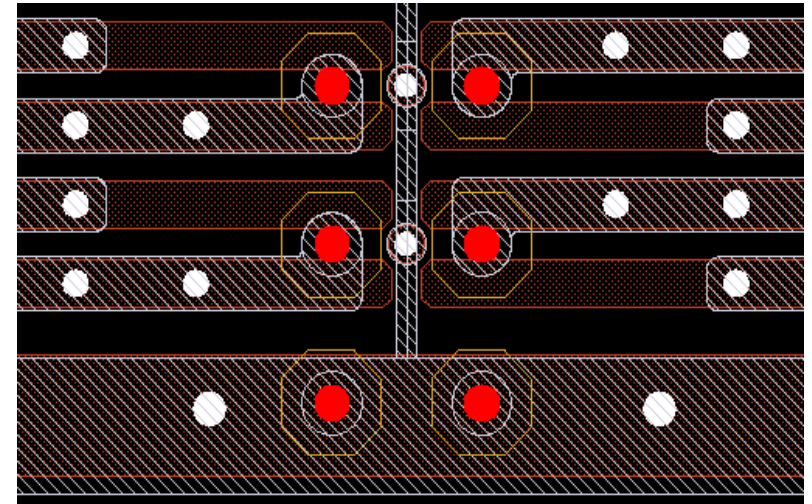
AC-coupling

All polysilicon bias resistors are
~100 squares long -> 300 kOhm



DC-coupling

Each group of 4 pixels share
one punch-through biasing dot



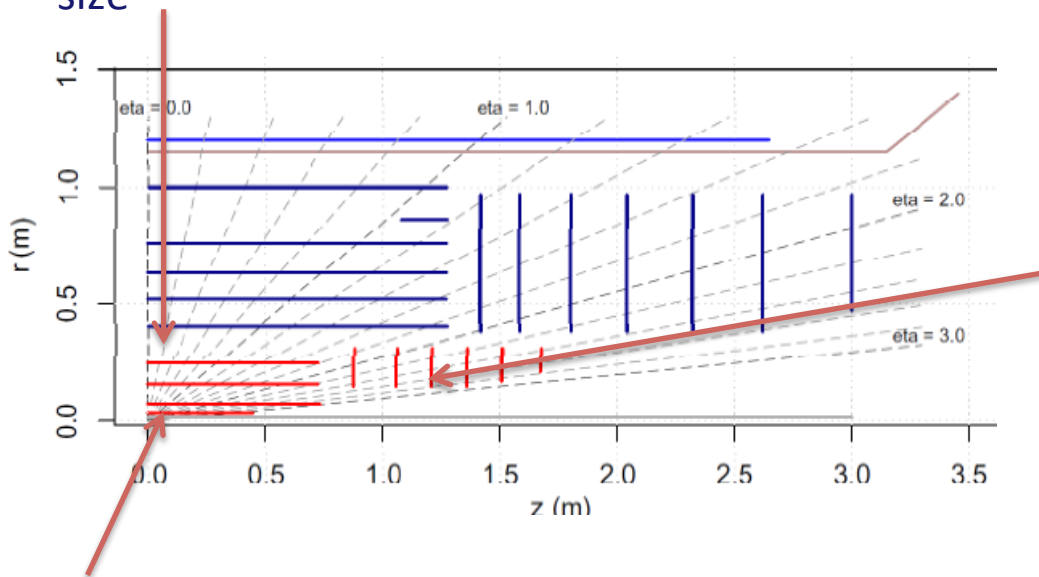
AC and DC coupled sensors are shuffled for the homogeneous etching of polysilicon ("minimum area coverage" DRC requirement)

Why study different pixel sizes?

Outer Barrel layers:

250x50 current baseline for outer barrel layers

Investigate using 500x25 device for outer barrel layers at high eta to reduce the cluster size



Pixel Endcap:

Investigate square modules for endcap (125x100 and 167x125)

Using the 167x125 would require turning off some channels

- less power/cooling

Inner barrel layer:

Plan to use FEI5 chip: 125x25. In order to study the pitch in x and y, we can study **125x100** and **500x25**

Why the different pixel sizes?

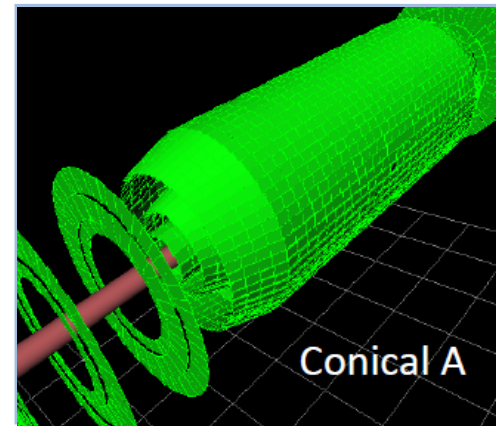
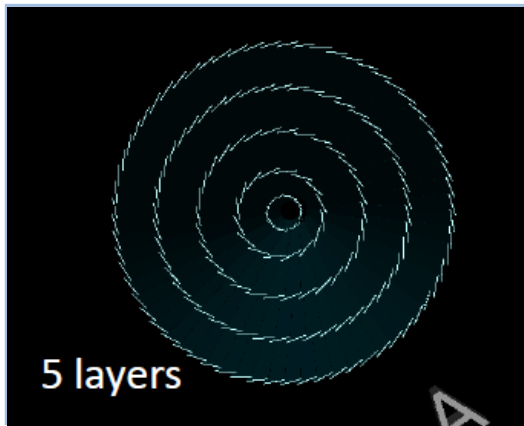
Alternative Tracker Geometries

The layout for the ITK is still being optimised, alternative layouts are being discussed (e.g. 5 pixel layers, conical layouts).

5th Pixel Layer

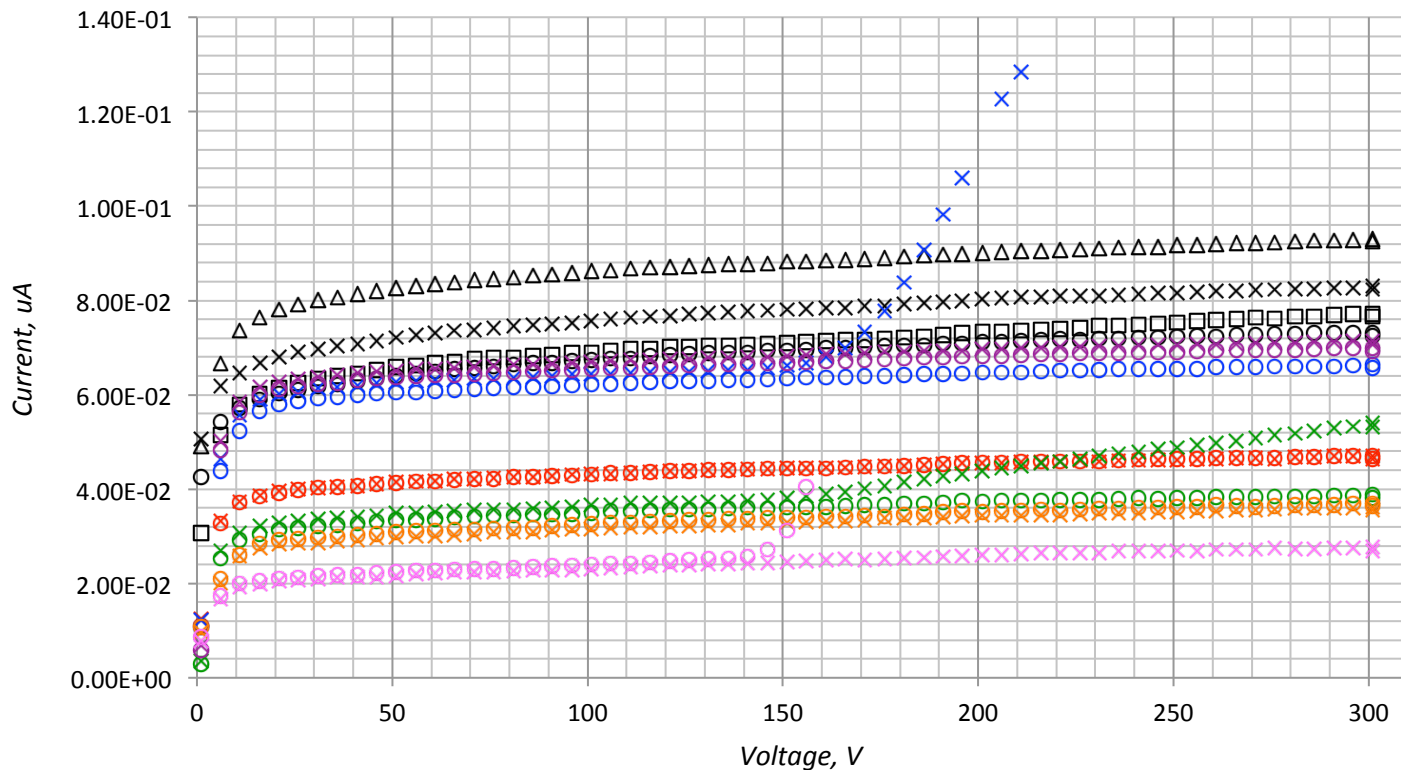
Investigate strixels (2000x25 and 2000x50): These should have better resolution than silicon strips.

These will again be dependent on switching off readout channels -> reduced power.



Alternate Geometry IV Characteristics

CP5 3072-3 300um IV



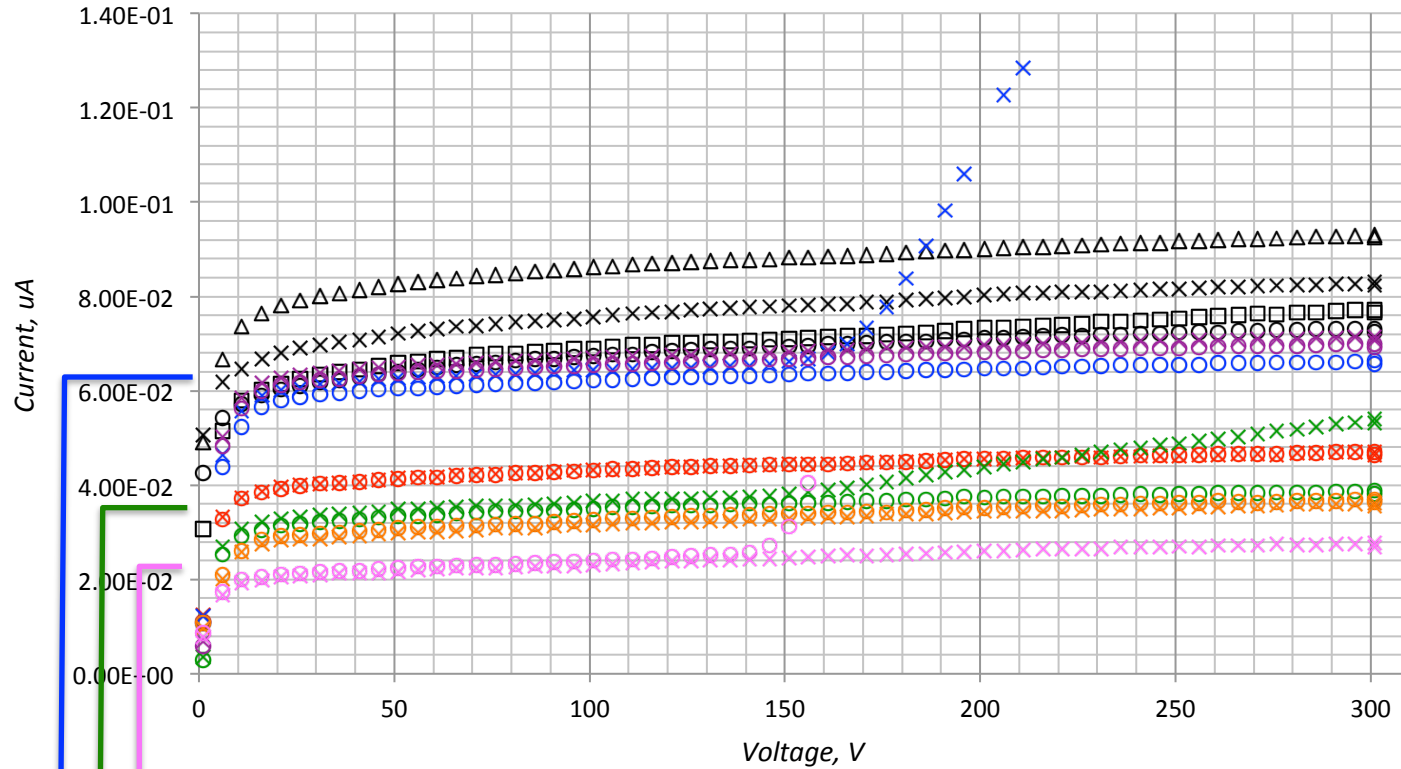
- CP5-3072-3-300UM-OPT1
- CP5-3072-3-300UM-OPT2
- △ CP5-3072-3-300UM-OPT3
- × CP5-3072-3-300UM-OPT4
- CP5-3072-3-300UM-250x50DC1
- × CP5-3072-3-300UM-250x50DC2
- CP5-3072-3-300UM-500x25DC1
- × CP5-3072-3-300UM-500x25DC2
- CP5-3072-3-300UM-2000x50DC1
- × CP5-3072-3-300UM-2000x50DC2
- CP5-3072-3-300UM-2000x25DC1
- × CP5-3072-3-300UM-2000x25DC2
- CP5-3072-3-300UM-125x100DC1
- × CP5-3072-3-300UM-125x100DC2
- CP5-3072-3-300UM-167x125DC1
- × CP5-3072-3-300UM-167x125DC2

Standard operating voltage is 150V

Devices bias up to 500V before Breakdown typically occurs (Not shown here)

Alternate Geometry IV Characteristics

CP5 3072-3 300um IV



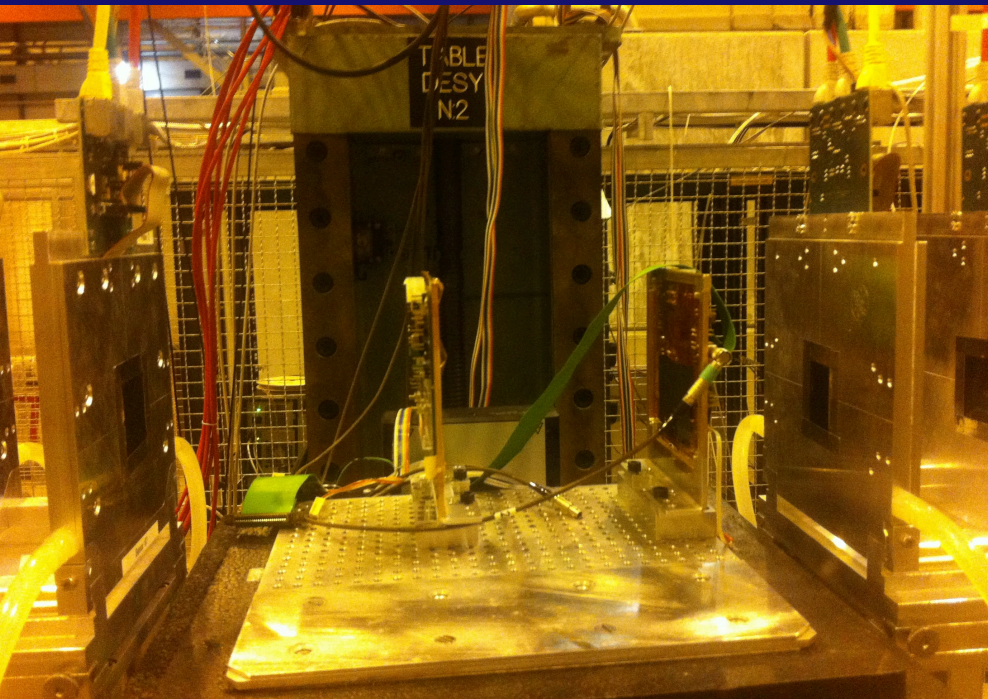
- CP5-3072-3-300UM-OPT1
- CP5-3072-3-300UM-OPT2
- △ CP5-3072-3-300UM-OPT3
- × CP5-3072-3-300UM-OPT4
- CP5-3072-3-300UM-250x50DC1
- × CP5-3072-3-300UM-250x50DC2
- CP5-3072-3-300UM-500x25DC1
- × CP5-3072-3-300UM-500x25DC2
- CP5-3072-3-300UM-2000x50DC1
- × CP5-3072-3-300UM-2000x50DC2
- CP5-3072-3-300UM-2000x25DC1
- × CP5-3072-3-300UM-2000x25DC2
- CP5-3072-3-300UM-125x100DC1
- × CP5-3072-3-300UM-125x100DC2
- CP5-3072-3-300UM-167x125DC1
- × CP5-3072-3-300UM-167x125DC2

Square devices

Devices with 50µm pitch in Y

Devices with 25µm pitch in Y

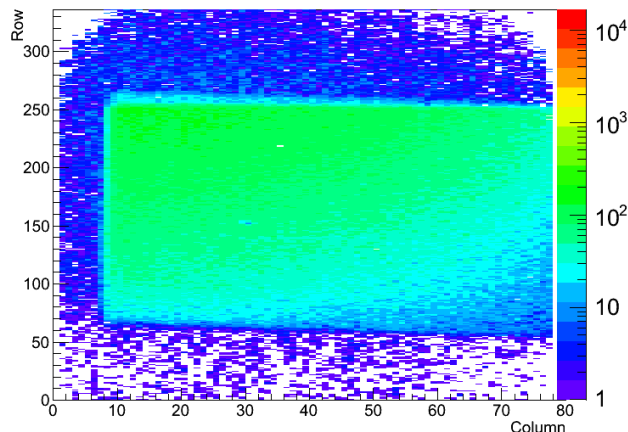
Local Density of PTB
dominates base leakage
current, not the total
number of PTB's



Pixels tested using 120GeV pions
6 MAPS sensors
2 Device Under Test (DUT)

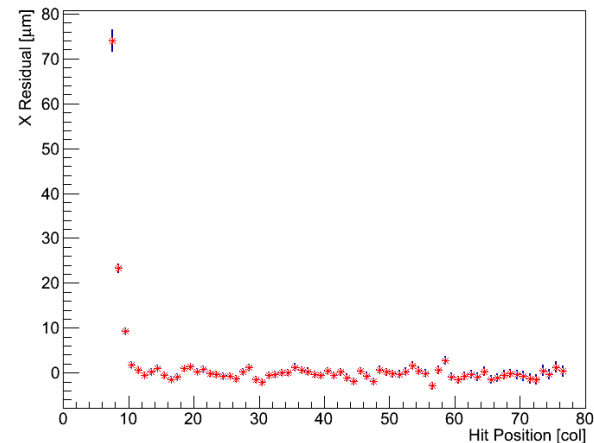


VTT5 Hitmap – all

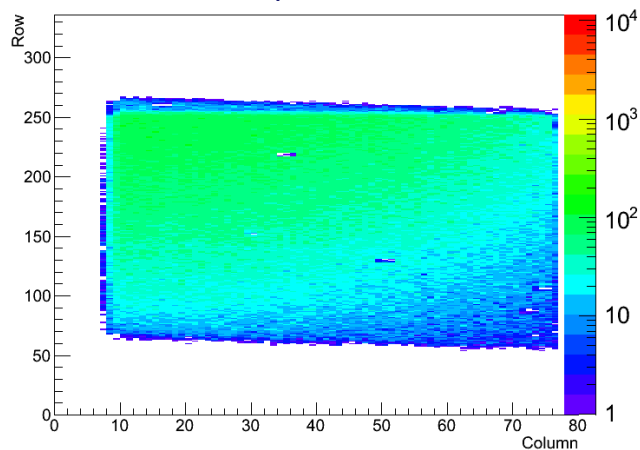


Residual vs Hit position are bad at outer region of matched track hitmap – due to limited scintillator size

Hit position X vs Residual X

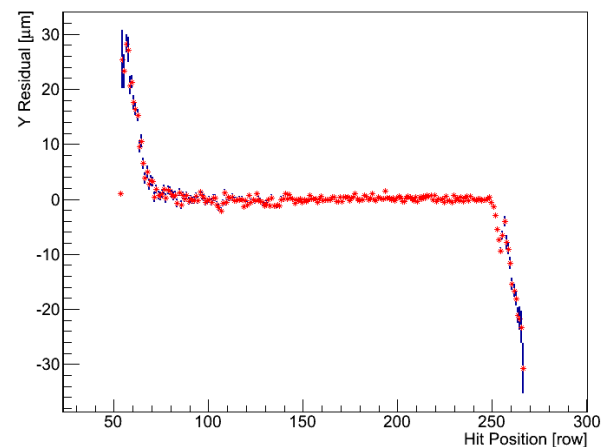


VTT5 Hitmap – matched tracks

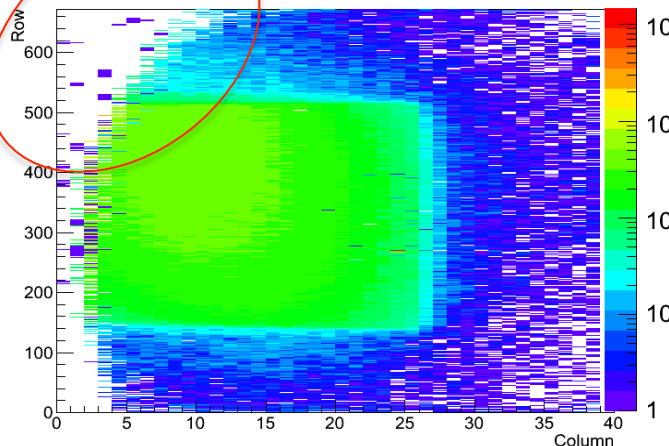


-> Use only central region for performance studies

Hit position Y vs Residual Y

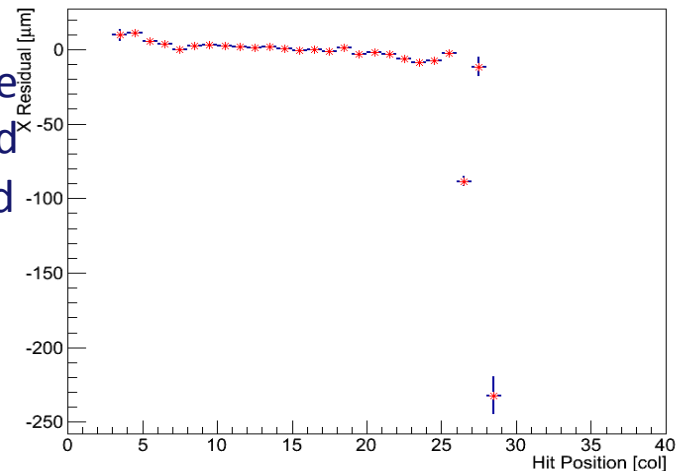


VTT10 Hitmap – all

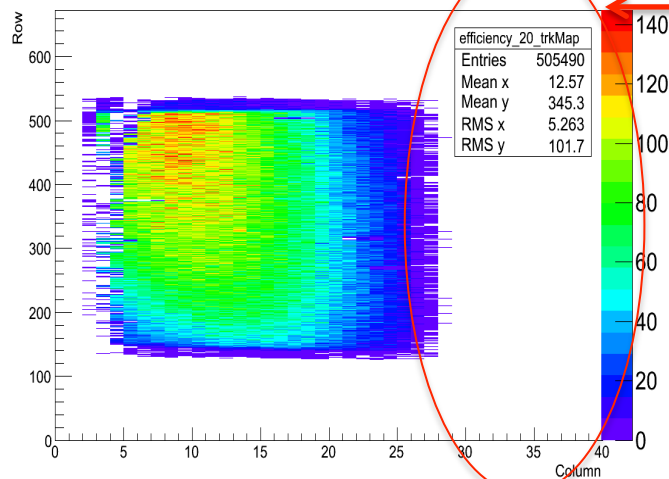


In this area, the readout chip is disconnected from the sensor pixels. Thinned readout chip was used during bump bonding to sensor - heat used (~300deg) caused the read out chip to bow.

Hit position X vs Residual X

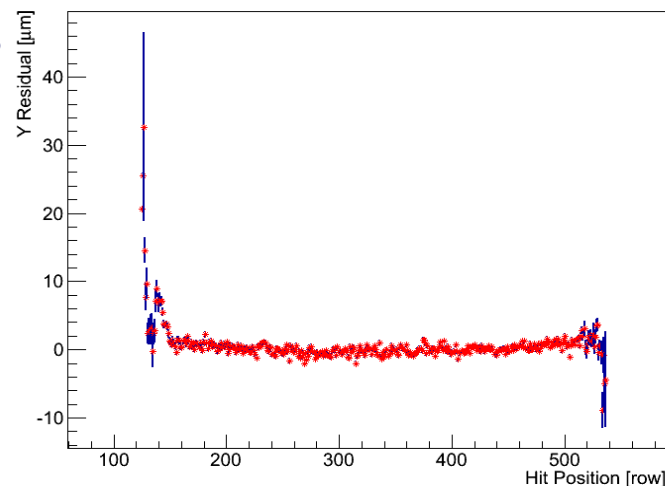


VTT10 Hitmap – matched tracks



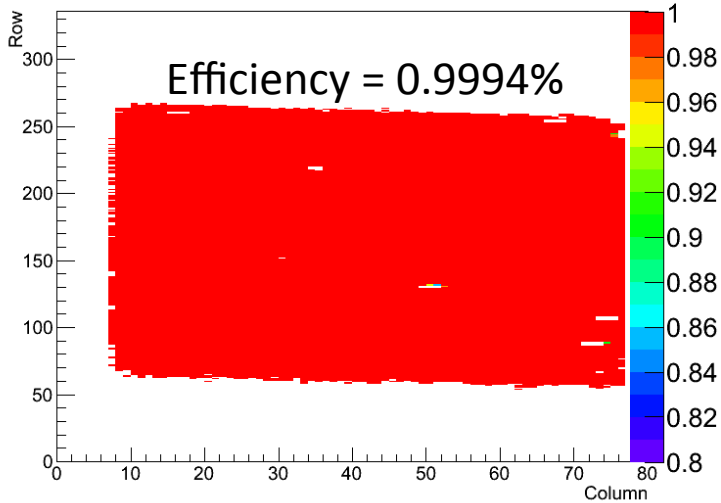
Alignment issues meant the device was not fully in the beam

Hit position Y vs Residual Y



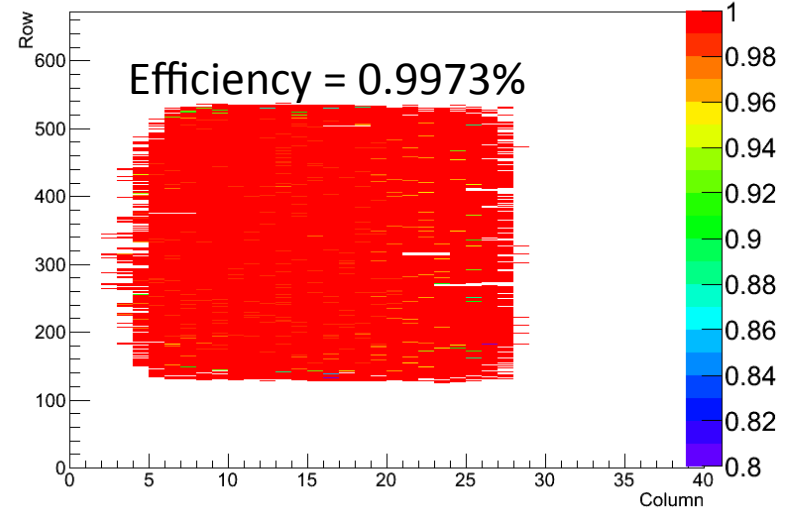
Sensor Efficiency - 250x50 (VTT5) vs 500x25(VTT10)

VTT5 3200e



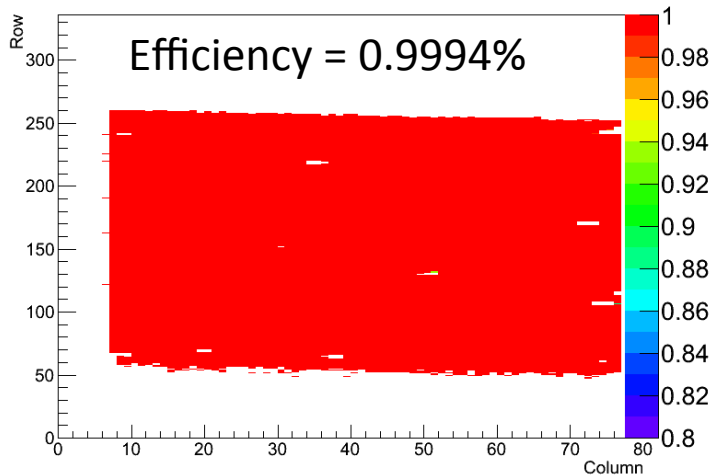
VTT10 show
same high
efficiency
performance
as VTT5

VTT10 3200e

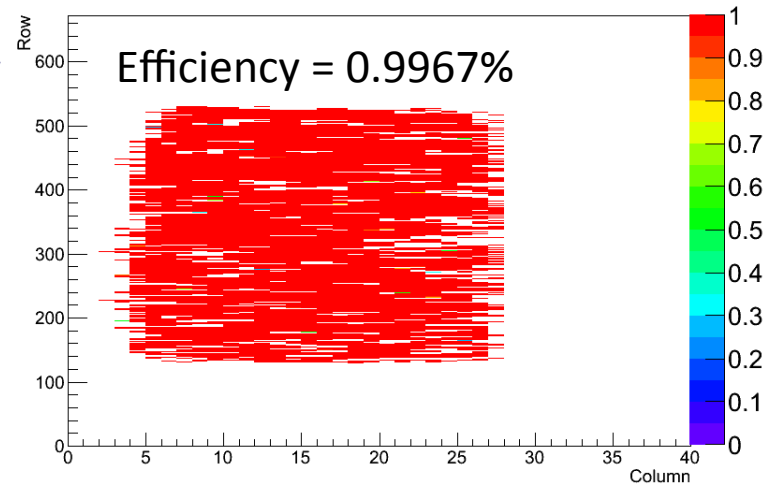


(small
degradation
due to quality
of tuning).

VTT5 1600e



VTT10 1600e

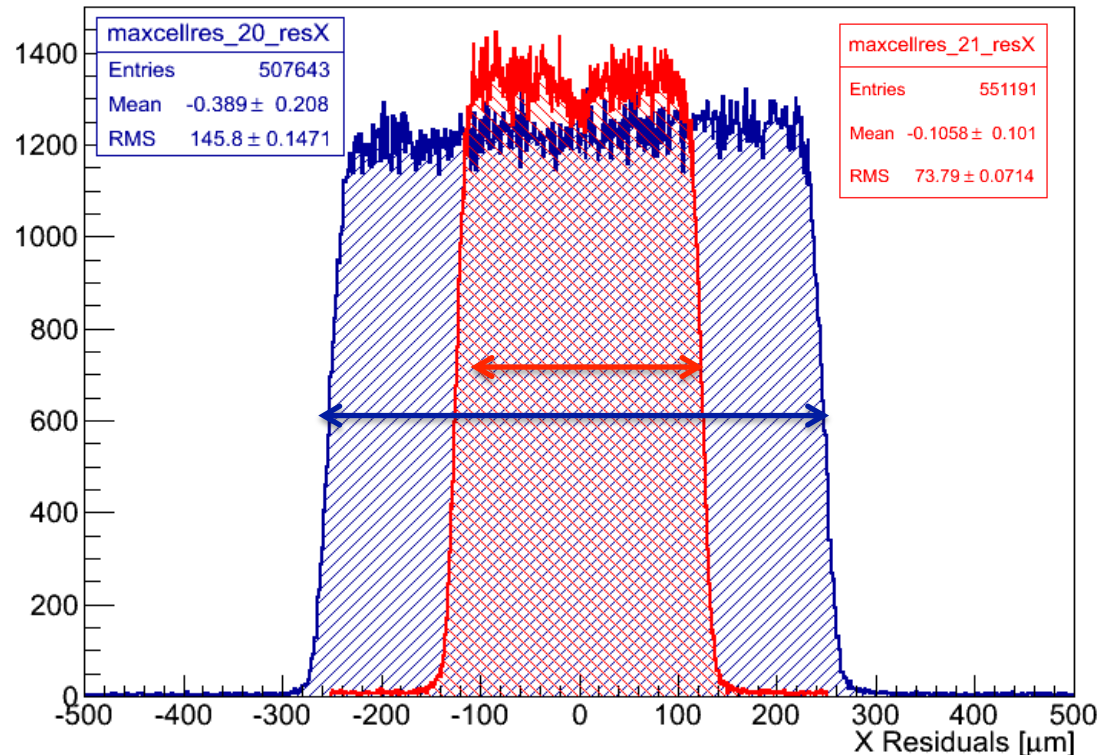


RMS values are approximately what is expected for pitch/root(12):

$$500 \times 25 : 500/\sqrt{12} = 144.3 \mu\text{m}$$

$$250 \times 50 : 250/\sqrt{12} = 72.17 \mu\text{m}$$

Width of distribution
(half way up) should be
500 for 500x25 and about
250 for 250x50

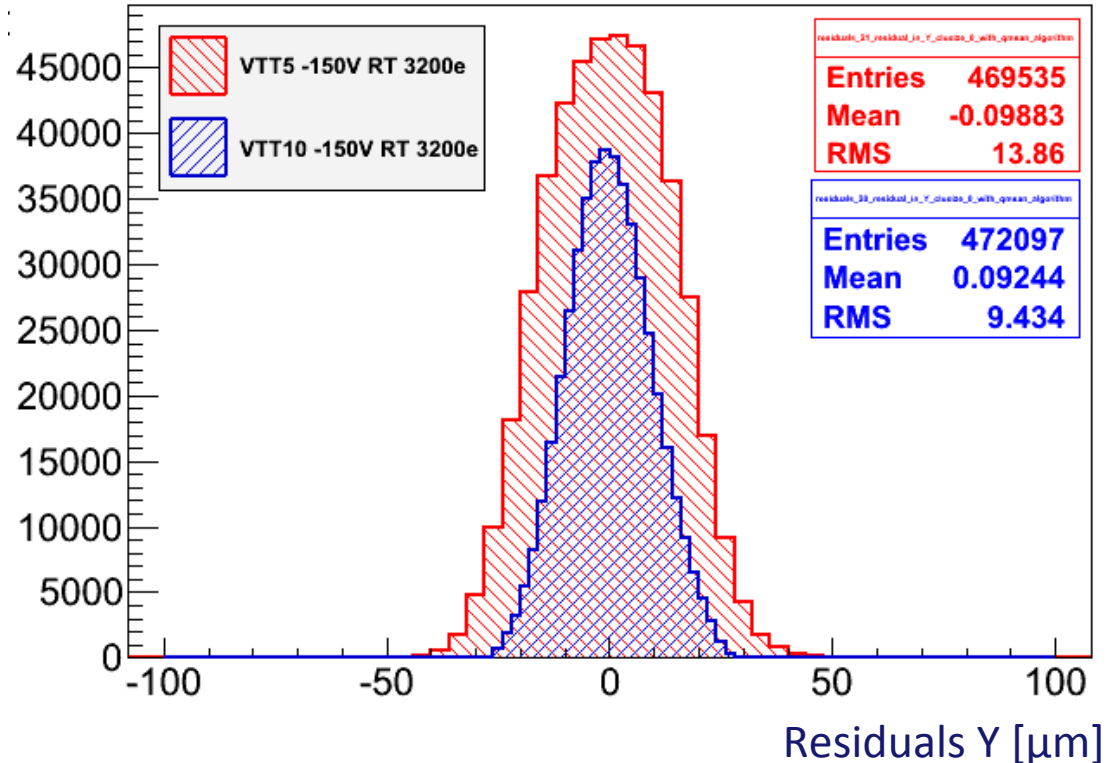


Residual Y and resolution – 250x50 vs 500x25

RMS values are approximately what is expected for pitch/root(12)

$$500 \times 25 : 25/\sqrt{12} = 7.217 \mu\text{m}$$

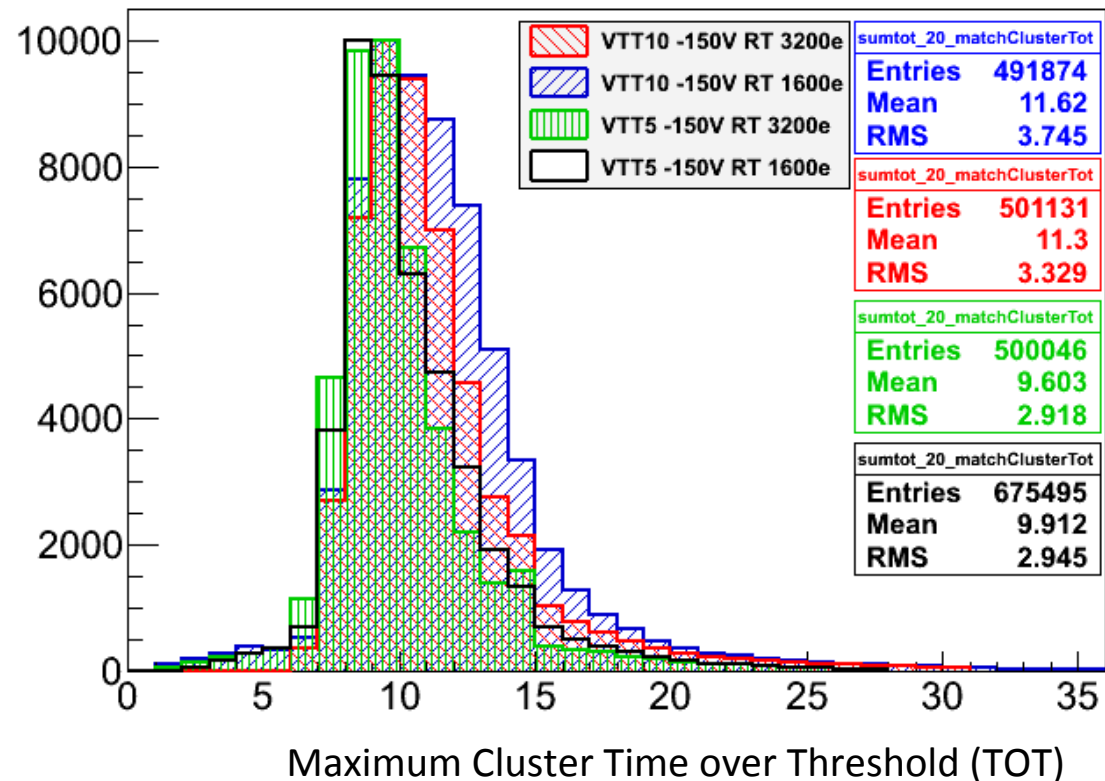
$$250 \times 50 : 50/\sqrt{12} = 14.43 \mu\text{m}$$

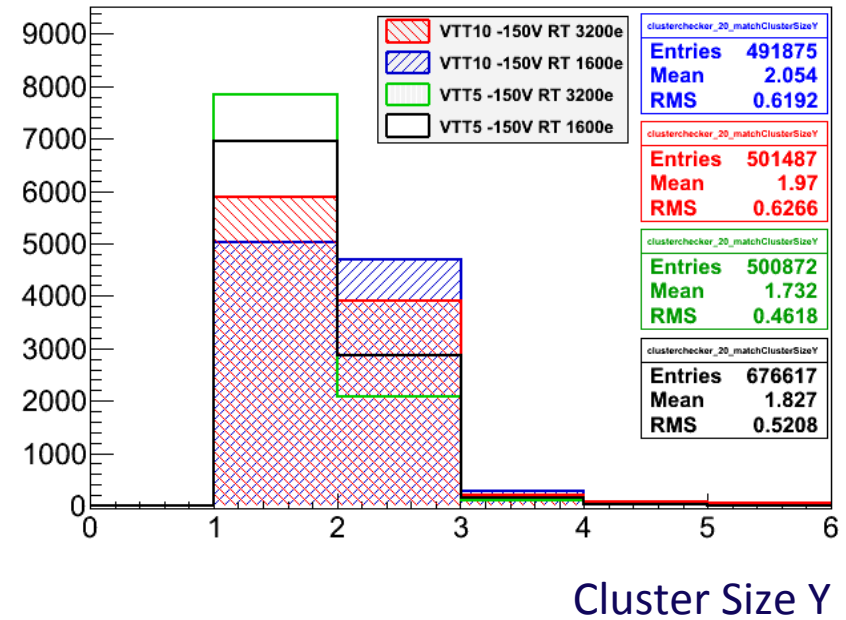
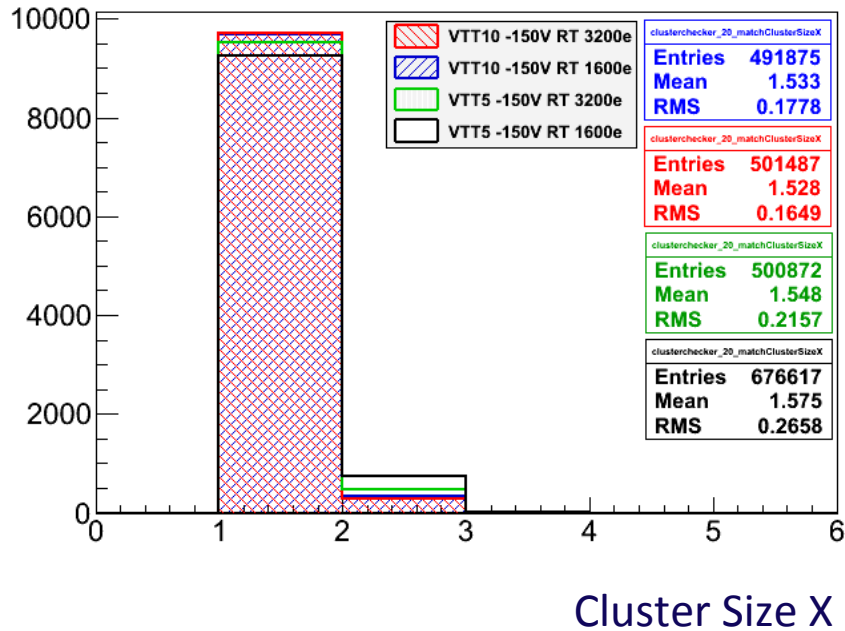


All device tunings are set for 10 ToT = 20ke

No real difference seen between different thresholds of the same device (500x25 and 250x50)

There is a slight difference between the tunings of the 500x25 and 50x250 devices



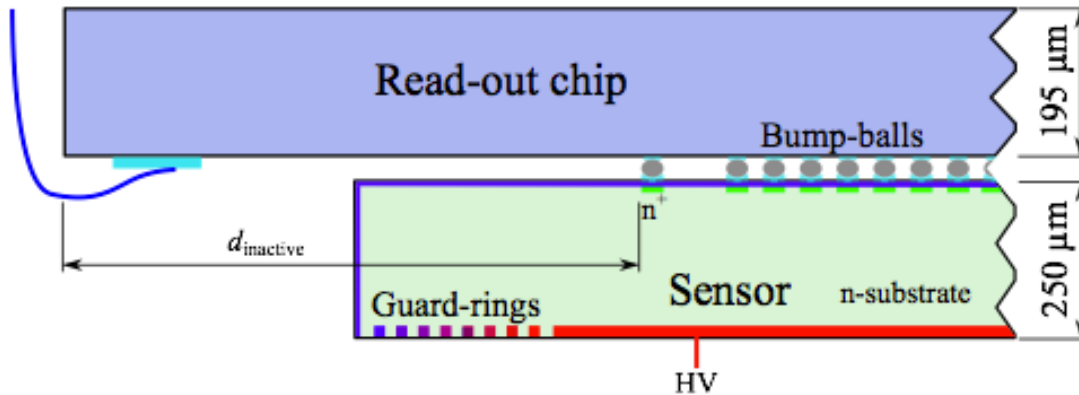


As expected :

- greater number of 2 hit clusters along Y in 500x25(VTT10)
 - Increased charge sharing
- Minimal change in cluster size in x-direction
 - (500x25 cluster size is slightly more skewed to 1 than 250x50(VTT5))

- We are studying different pixel geometries that could be part of the ATLAS ITK
- We are starting with basic measurements at 0degrees, for unradiated $25 \times 500 \mu\text{m}^2$ modules
 - The CERN pixel V has improved electrical characteristics
 - Basic characteristics such as efficiency and residuals are looking sensible
 - Cluster Size
 - Minimal difference in x
 - Increased charge sharing in y
- We can now progress to studying :
 - Radiated pixel studies
 - High Eta studies
 - Data available, but not yet reconstructed
 - 125×500
 - Data available, but not yet reconstructed
 - AC coupling

BACKUP

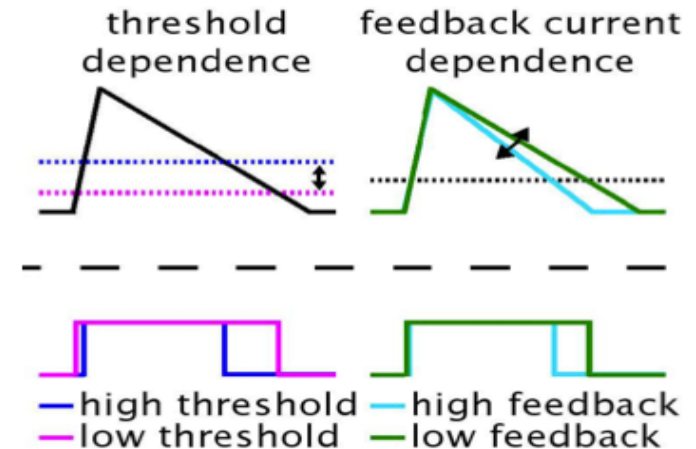


Sensor design

- DOFZ Si n-substrate, 250 μm thick
- Read-out chip planar n+-in-n pixels, 400x50 μm^2
- 16 guard rings on p side to shape HV step
- 1.1 mm inactive edge incl. safety margin

Read-out and interconnection

- FE-I3: 2880 channels
- DC coupled and bump bonding
- Shaper + Amplifier + Discriminator
- $\text{ToT} \propto \text{Charge}$





Choosing a device thickness

Thinner devices retain, a greater fraction of Collected Charge (CC) than thicker devices after irradiation

Graphs show the CC vs received fluence for strip devices at 600V and 1000V

Low threshold operation of FE-I4 enables thin devices to be used.

